

Heubach formulation No. 891-02

10/18

FUNCTION	PRODUCT	PRODUCER	PBW
Component A			
Styrene-acrylic	WorléeCryl VP A 2117/75 BA	Worlée	30.15
Rheology modifier	WorléeAdd 820 paste, 10% in xylene	Worlée	1.70
Wetting and dispersing agent	Disperbyk-167	Byk	0.40
Thickening agent	Hi-Sil T 800	PPG	0.15
Solvent	Solvesso 100	Exxon	3.35
Solvent	Butyl acetate		3.10
Anticorrosive pigment	HEUCOPHOS® ZAM-PLUS	Heubach	3.90
Magnesium silicate	Finntalc M15	Mondo Minerals	5.55
Mica/Quartz/Chlorite	Plastorit Micro	Imerys	6.90
Magnesium calcium carbonate	Microdol 1	Omya	20.25
Titanium dioxide	Kronos 2310	Kronos	8.30
Iron oxide yellow	Bayferrox 420	Lanxess	0.50
Pigment black	Monarch 430	Cabot	0.05
Grind with a bead mill.			
Silicone polyether additive	Dow Corning 205 SL	Dow Corning	0.20
Solvent	Solvesso100/Butyl acetate 52:48		8.00
			92.50
Component B			
Polyisocyanate	Tolonate HDT LV	Vencorex	4.50
Solvent	Butyl acetate		3.00
			7.50
			100.00
Mix components A and B thoroughly prior to use.			
SPECIFICATIONS			

HEUCOPHOS[®] ZAM-PLUS

In high solids polyurethane



Solvent based

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Vol.-% Anticorrosive pigment reg. pigment/filler	7.5
PVC in %	27.3
PVC / CPVC	0.6
Solids in %	73.2
Crosslinking in %	100.0

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